

b' Good.

~~a base for holding [remaining constituent] the following elements;~~
~~a scanning stage moved, with respect to said base, along a first direction~~
~~corresponding to a moving direction of said mask and said substrate;~~
~~a fine adjustment stage, arranged to be freely moved within predetermined~~
~~ranges in the first direction and in a second direction perpendicular to the first direction with~~
~~respect to said scanning stage, for mounting one of said mask and said substrate thereon;~~
~~a first electromagnetic actuator for driving said fine adjustment stage in the~~
~~second direction with respect to said scanning stage; and~~
~~a second electromagnetic actuator for driving said fine adjustment stage in the~~
~~first direction with respect to said scanning direction, and generating a larger thrust than that~~
~~of said first electromagnetic actuator upon reception of the same input as that provided to said~~
~~first electromagnetic actuator.~~

Claim 11, line 9, change "remaining constituent" to --the following--.

b'

16. (Amended) A drive table which is two-dimensionally driven, comprising:
~~a base for holding [remaining constituent] the following elements;~~
~~a table for mounting an object thereon;~~
~~a driving system for two-dimensionally driving said table, with respect to said~~
~~base, along a plane defining [on which] an X-Y reference coordinate system [is set], said X-Y~~
~~reference coordinate system being fixed to said base;~~
~~a position detection unit for detecting a position of said table;~~
~~a reference position detection unit for generating a detection signal when a~~
~~predetermined point on said table reaches a predetermined reference position on said X-Y~~
~~reference coordinate system; and~~

~~a calculation unit for converting a detection value from said position detection unit into a coordinate value in said X-Y reference coordinate system in accordance with the detection signal obtained from said reference position detection unit and a detection value from said position detection unit, which is obtained upon generation of the detection signal.~~

Claim 19, line 1, before "said" insert --wherein--.

Claim 27, line 24, change "Wherein" to --wherein--.

Please add the following claims 28-31:

--28. A lithographic device comprising the following elements which are supported in that order:

a substrate stage which can be positioned by a first positioning device parallel to a Y-direction which is perpendicular to a vertical Z-direction and an X-direction which is perpendicular to the Y-direction and to the Z-direction;

an imaging system with a main axis directed parallel to the Z-direction;

a mask stage which can be positioned parallel to the Y-direction by a second positioning device; and

an illumination optical system which irradiates an exposure illumination light beam;

wherein the mask stage is also positionable parallel to the X-direction and rotatable about an axis of rotation which is parallel to the Z-direction by the second positioning device; and

wherein the second positioning device is provided with a first linear motor by means of which the mask stage can be positioned over comparatively small movement parallel to the Y-direction and X-direction and can be rotated about the axis of rotation of the

mask stage and a second linear motor by means of which the mask stage can be positioned over comparatively great movement parallel to the Y-direction.--

B2 Cont'd.
Subj. c --29. The lithographic device as claimed in claim 28, wherein the magnet system and ^{an} the electric coil system belong to the first linear motor, while the second linear motor comprises a stationary part and a movable part which is displaceable parallel to the Y-direction over a guide of the stationary part, the magnet system of the first linear motor being fastened to the mask stage and the electric coil system of the first linear motor being fastened to the movable part of the second linear motor.--

--30. A lithographic device comprising the following elements which are supported in that order:

a substrate stage which can be positioned by a first positioning device parallel to a first direction which is perpendicular to a vertical Z-direction and a second direction which is perpendicular to the first direction and to the Z-direction;

an imaging system with a main axis directed parallel to the Z-direction;

a mask stage which can be positioned parallel to the first direction by a second positioning device; and

an illumination optical system which irradiates an exposure illumination light beam;

wherein the mask stage is also positionable parallel to the second direction and rotatable about an axis of rotation which is parallel to the Z-direction by the second positioning device; and

wherein the second positioning device is provided with a first linear motor by means of which the mask stage can be positioned over comparatively small movement parallel to the first direction and the second direction and can be rotated about the axis of